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(12) **United States Design Patent**
Kimura

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(54) **WAFER HOLDER FOR ION IMPLANTATION**

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(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **13-03**
(52) **U.S. Cl.**
USPC **D13/182**
(58) **Field of Classification Search**
USPC D13/182; 118/500, 728, 729; 414/217, 414/222.01, 416.03, 935, 936, 937, 938, 414/939, 940, 941; 156/345.51, 345.52, 156/345.53
See application file for complete search history.

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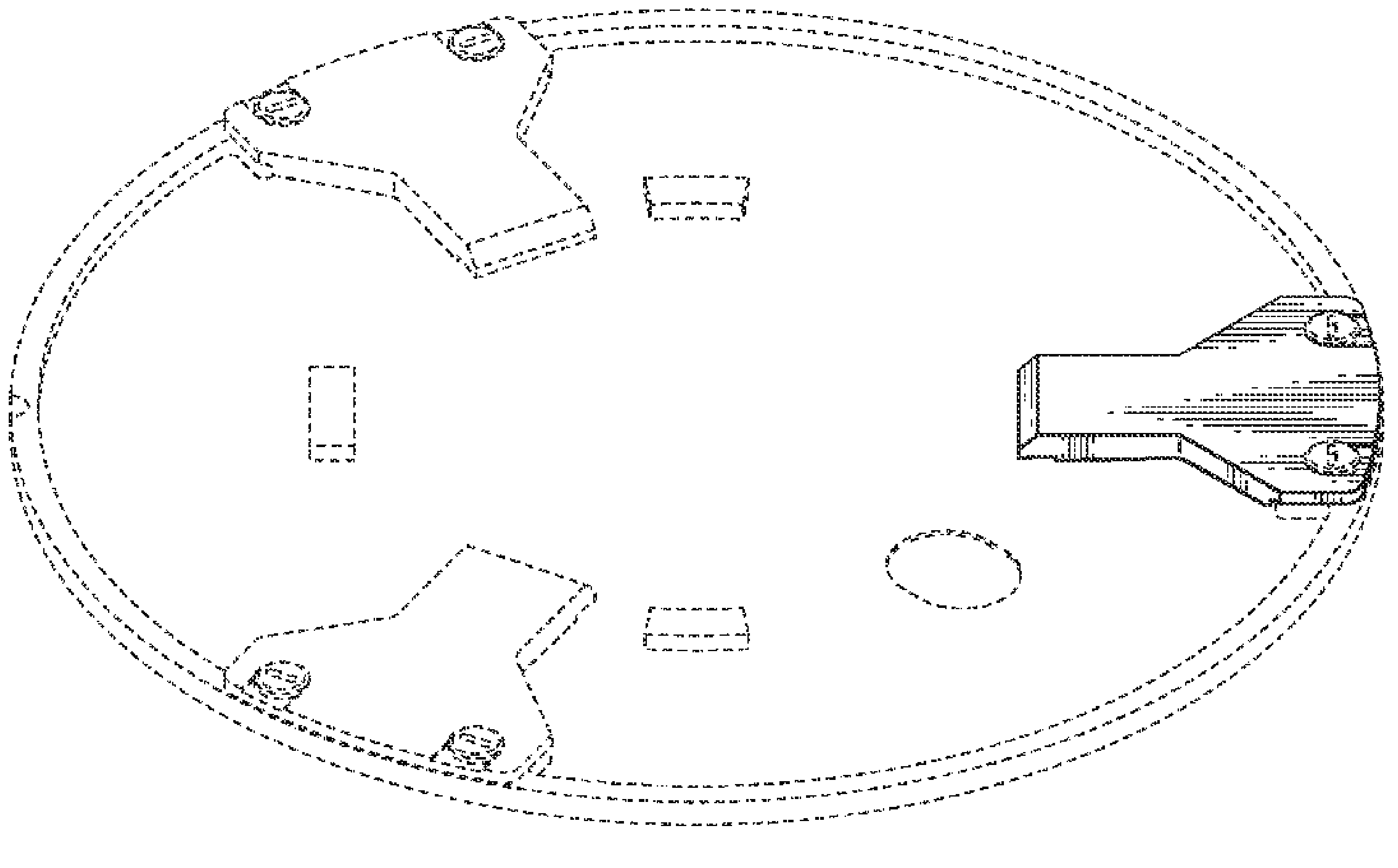
(57) **CLAIM**

The ornamental design for a wafer holder for ion implantation, as shown and described.

DESCRIPTION

FIG. **1** is a front view of a wafer holder for ion implantation, which is an apparatus used in the manufacture of integrated circuits, specifically used to fix the wafer to an ion implantation device to perform the process of ion implantation into the wafer by ion beam, showing my new design;
FIG. **2** is a rear view thereof;
FIG. **3** is a top plan view thereof;
FIG. **4** is a bottom plan view thereof;
FIG. **5** is a right side view thereof;
FIG. **6** is a left side view thereof;
FIG. **7** is a perspective view thereof;
FIG. **8** is an enlarged cross sectional view taken along line **8-8** of FIG. **3** thereof;
FIG. **9** is an enlarged cross sectional view taken along line **9-9** of FIG. **3** thereof;
FIG. **10** is a bottom perspective view of the arm thereof, wherein the arm is shown removed for ease of illustration; and,
FIG. **11** is an enlarged perspective view of a portion taken along line **11-11** of FIG. **10** thereof.
The broken lines shown in the drawings represent portions of the wafer holder for ion implantation that form no part of the claimed design.

1 Claim, 9 Drawing Sheets



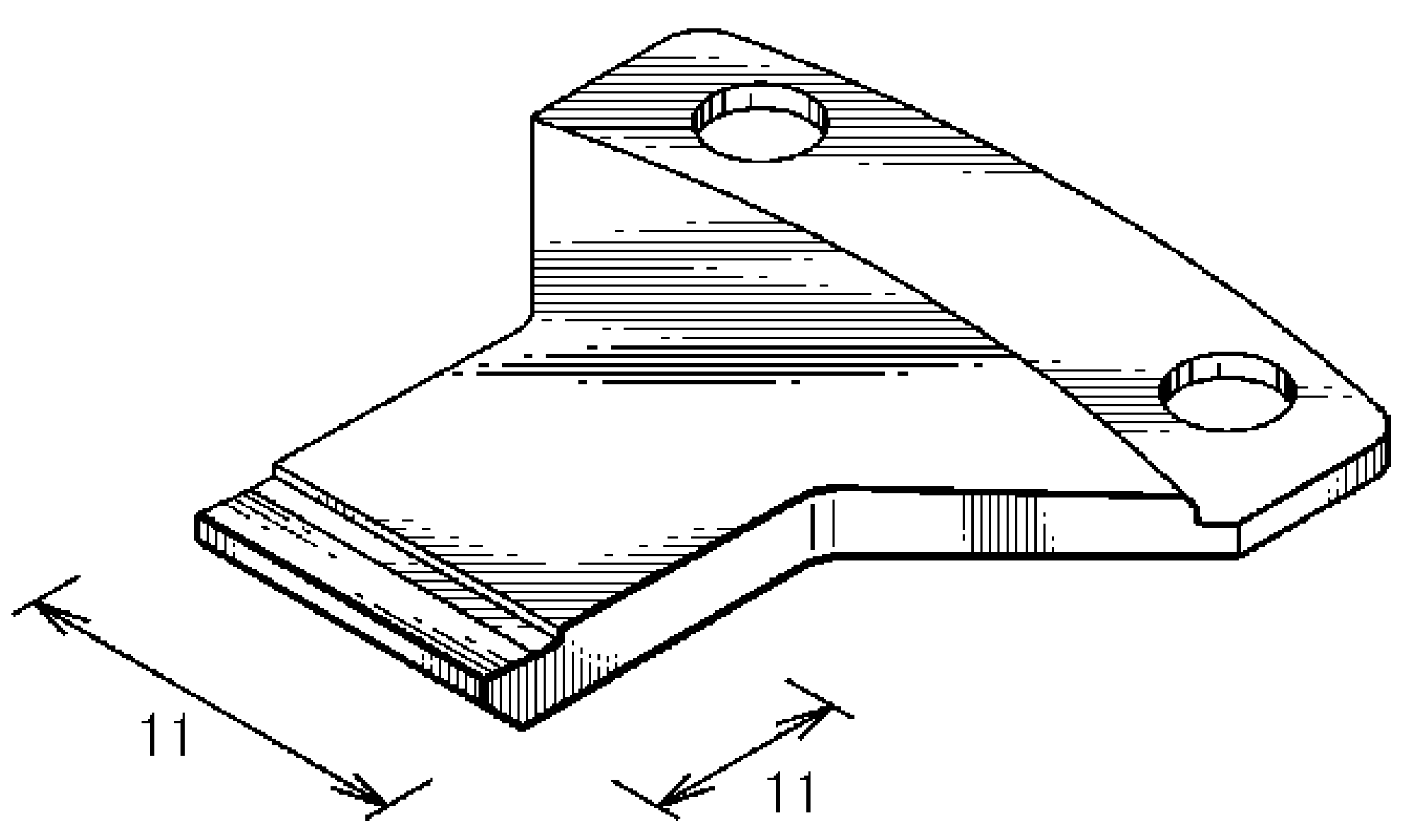


FIG. 1

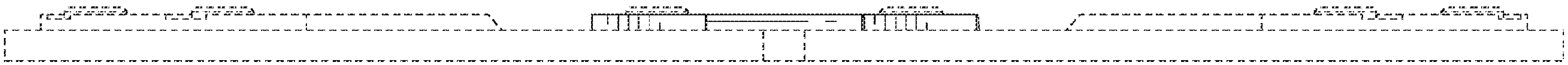


FIG.2

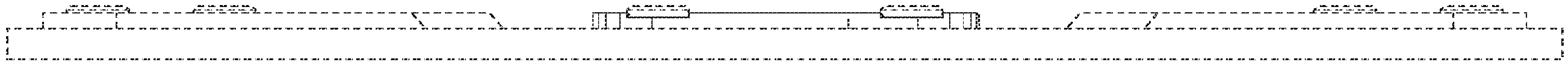


FIG.3

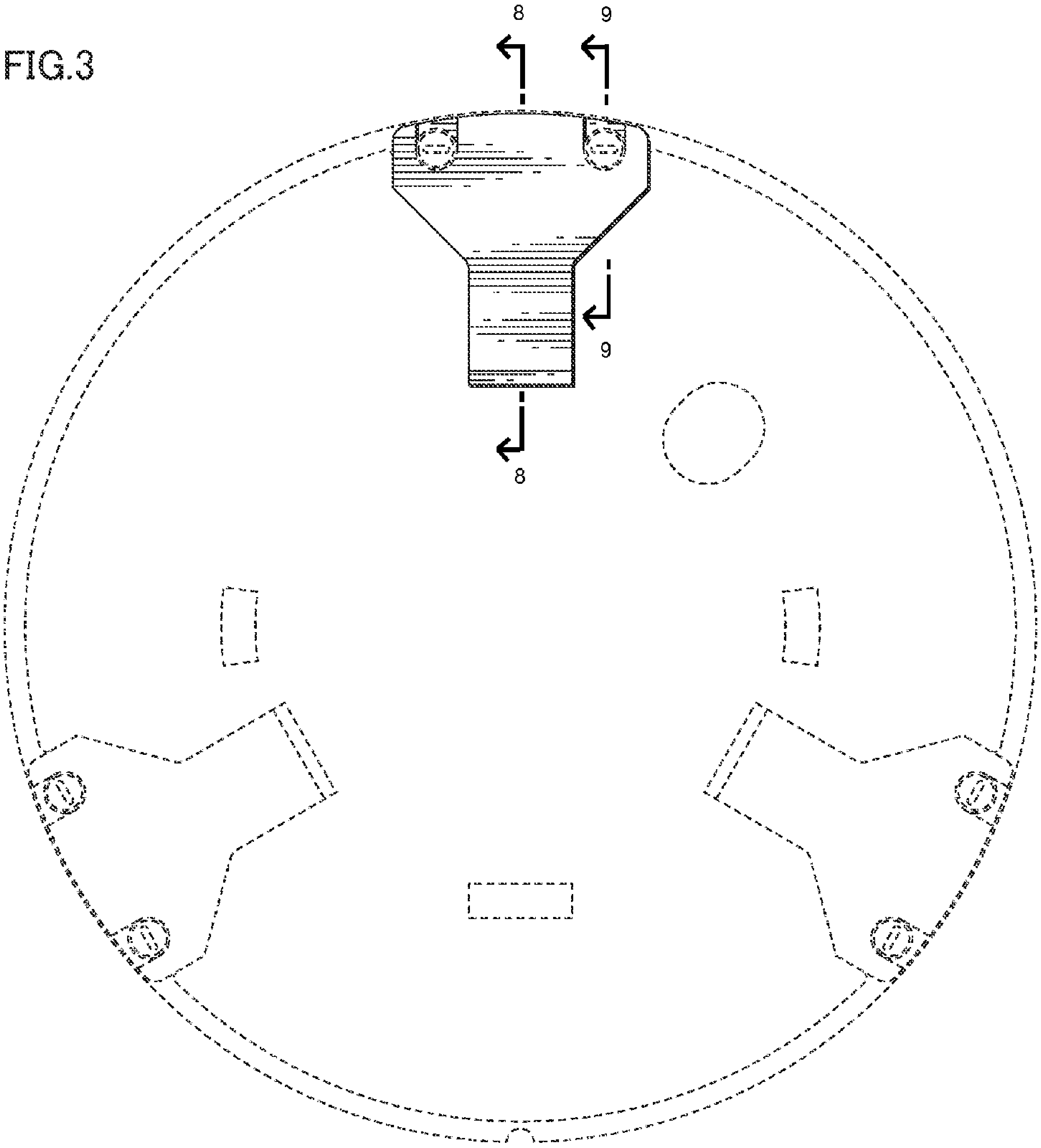


FIG.4

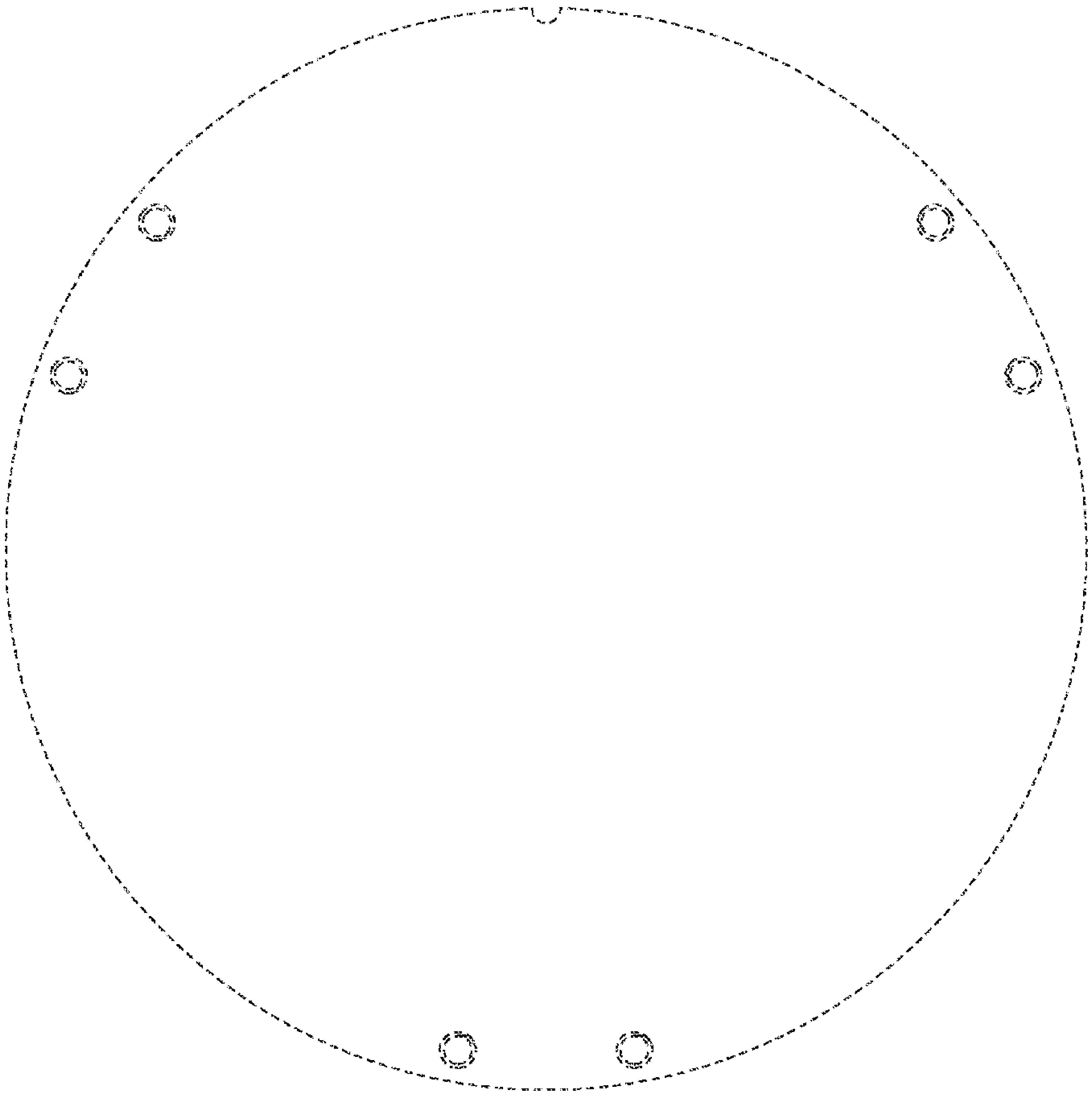
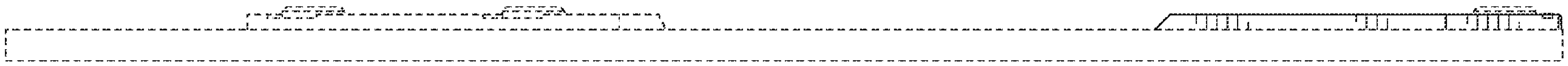


FIG.5



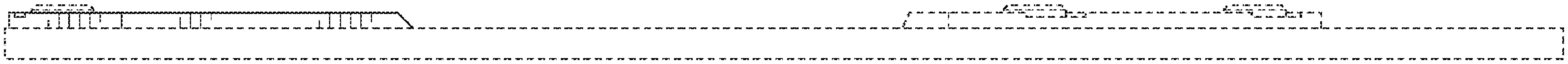


FIG.6

FIG.7

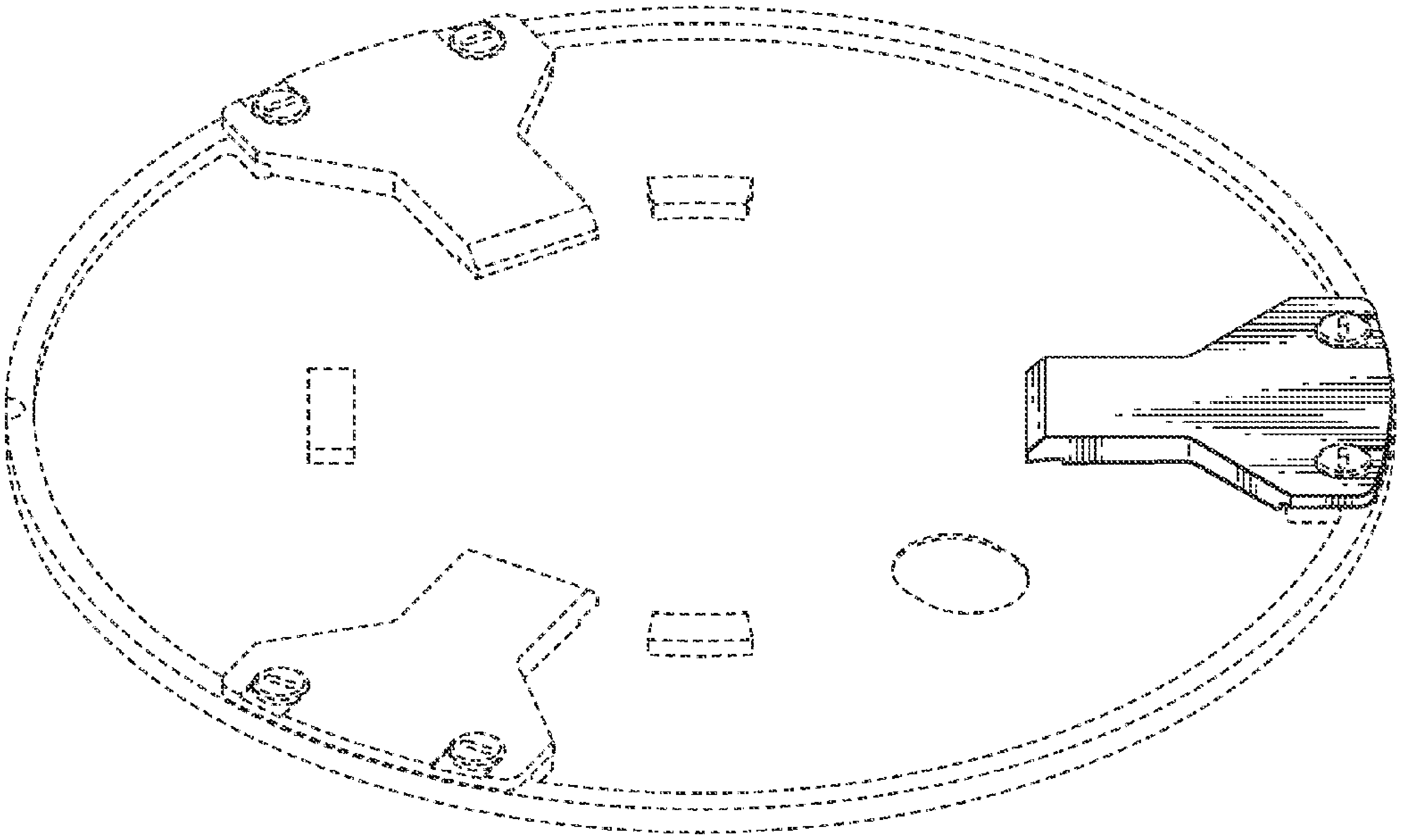


FIG.8

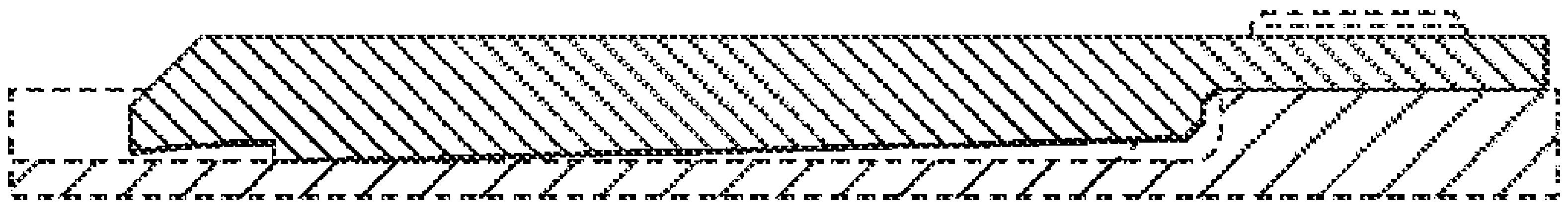


FIG.9

FIG.10

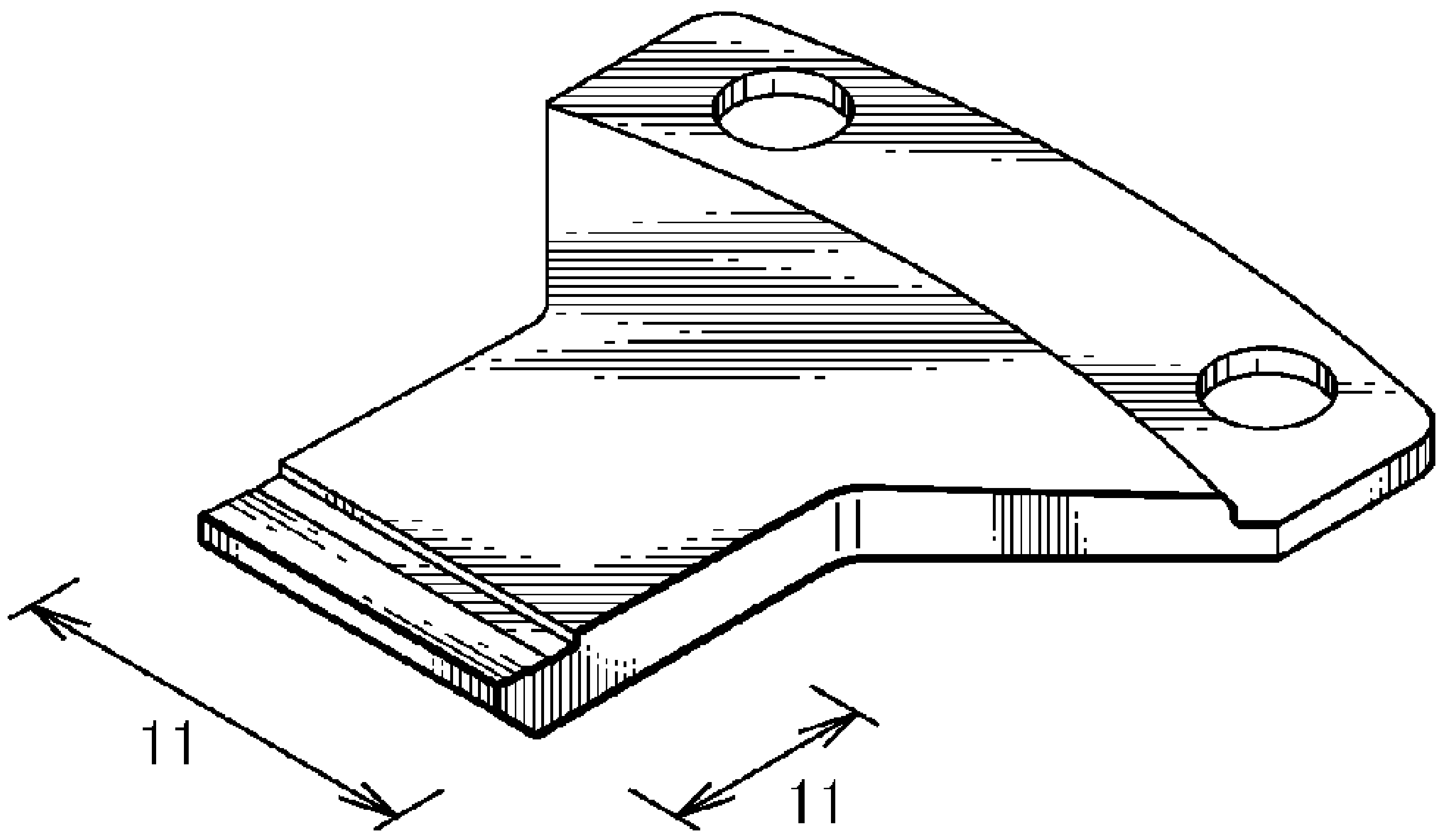


FIG.11